

Docket No.: 60188-596

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of	:	Customer Number: 20277
	:	
Akio MISAKA	:	Confirmation Number:
	:	
Serial No.: Divisional of Appl. No.		
09/869,848	:	Group Art Unit:
	:	
Filed: October 21, 2003	:	Examiner:
	:	
For: A PATTERNING METHOD USING A PHOTOMASK		

**INFORMATION DISCLOSURE STATEMENT**

Mail Stop Information Disclosure  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

The references were cited by or submitted to the U.S. Patent and Trademark Office in parent application Serial No. 09/869,848, filed July 6, 2001, which is relied upon for an earlier

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filing date under 35 USC 120. Thus, copies of these references are not attached. 37 CFR 1.98(d).

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT, WILL & EMERY

A handwritten signature in black ink, appearing to be 'Michael E. Fogarty', written over the printed name.

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**Date: October 21, 2003**

<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>				ATTY. DOCKET NO. <b>60188-596</b>		SERIAL NO. <b>Divisional f Appl. No.</b> <b>09/869,848</b>	
(PTO-1449)				APPLICANT <b>Akio MISAKA</b>			
				FILING DATE <b>October 21, 2003</b>		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		US	5,354,632	08/11/1994	Dao et al.		
		US	5,908,718	06/01/1999	Ishida et al.		
		US	5,718,829	02/1998	Pierrat		
		US	5,733,687	03/1998	Tanaka et al.		
		US	5,766,805	06/1998	Lee et al.		
		US	5,824,438	10/1998	Choi et al.		
		US	6,044,007	03/2000	Capodieci		
		US	6,083,275	07/2000	Heng et al.		
		US					
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		US					
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		JP 3-11345 A	01/18/1991				
		JP 10-326005 A	12/08/1998				
		JP 7-72612 A	03/17/1995				
		EP 0 401 795 A	12/12/1990	OKI ELECTRIC IND. CO., LTD.			
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
		H.Y. LIU et al., "The Application of Alternating Phase-shifting Masks to 140nm Gate Patterning (II): Mask Design and Manufacturing Tolerances", Proceedings of SPIE, Vol. 3334, pp. 2-14, February 1998.					
		H. WATANABE et al., "Transparent Phase Mask", The 51th Annual Technical Meeting of the Japan Society of Applied Physics, 27p-ZG-1, p. 490, September 1990.					
EXAMINER				DATE CONSIDERED			

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.